

ABSTRACT

APPARATUS FOR VACUUM DEPOSITION WITH A RECHARGING RESERVOIR AND CORRESPONDING PROCESS FOR VACUUM DEPOSITION

The present invention relates to a vacuum deposition apparatus comprising an enclosure (1) adapted to receive a substrate (2) to be treated and to be placed under a vacuum and at least one injector (110) for generating a molecular beam of vapor of an organic material. The injector, provided with a valve (20), traverses the bottom of the enclosure and comprises a nozzle (120) adapted for receiving a removable reservoir (10) containing this organic material. A main heating apparatus (50) heats the reservoir and secondary heating apparatuses (30, 40) heat the injector in such a manner as to establish a temperature gradient.

Fig. 1